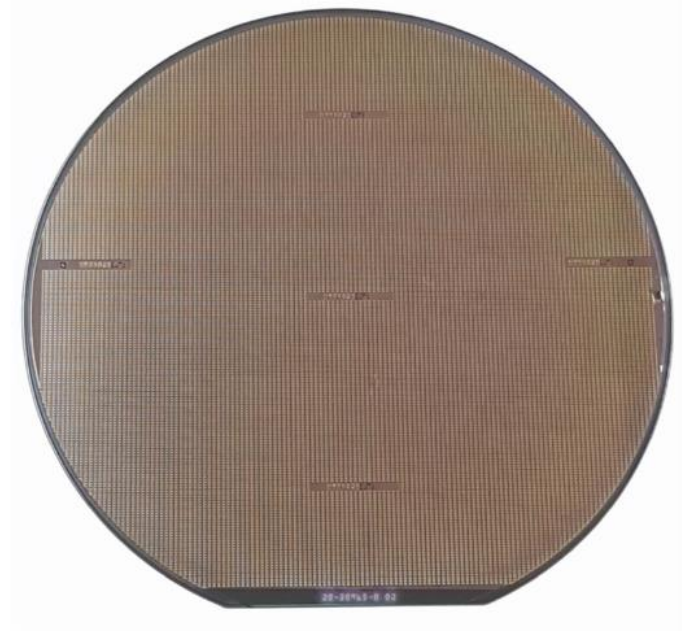


## GaN FET Processed Wafers (6 inch GaN on Si)

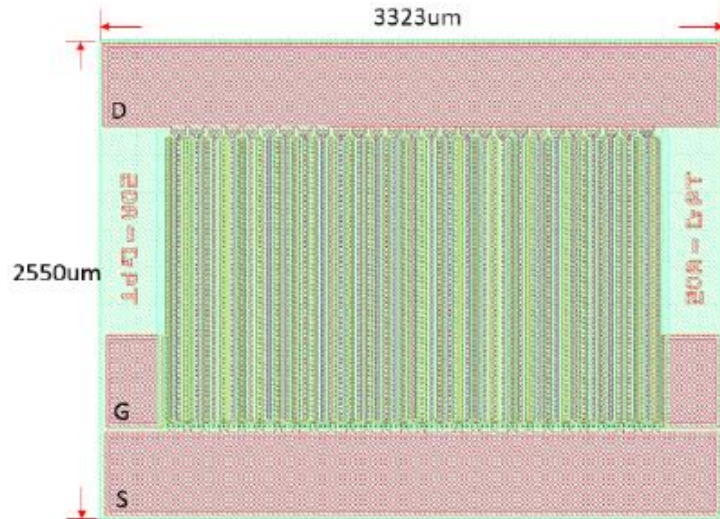
- D-mode FET fabricated on 6 inch GaN on Si wafers
  - 3 models are available (140mA, 15A, 25A)
  - Customers can shorten the development turn-around time to save the resources
- 
- Performance :
    - Breakdown voltage: > 650V
    - High speed switching
    - Low ON resistance

Die Wafer: w/BGBM, w/o Dicing



# (Example) GaN FET Device Characteristics (25A)

Ex:GPT YBE 15-25A



Chip design

## Chip Specification:

25A HEMT

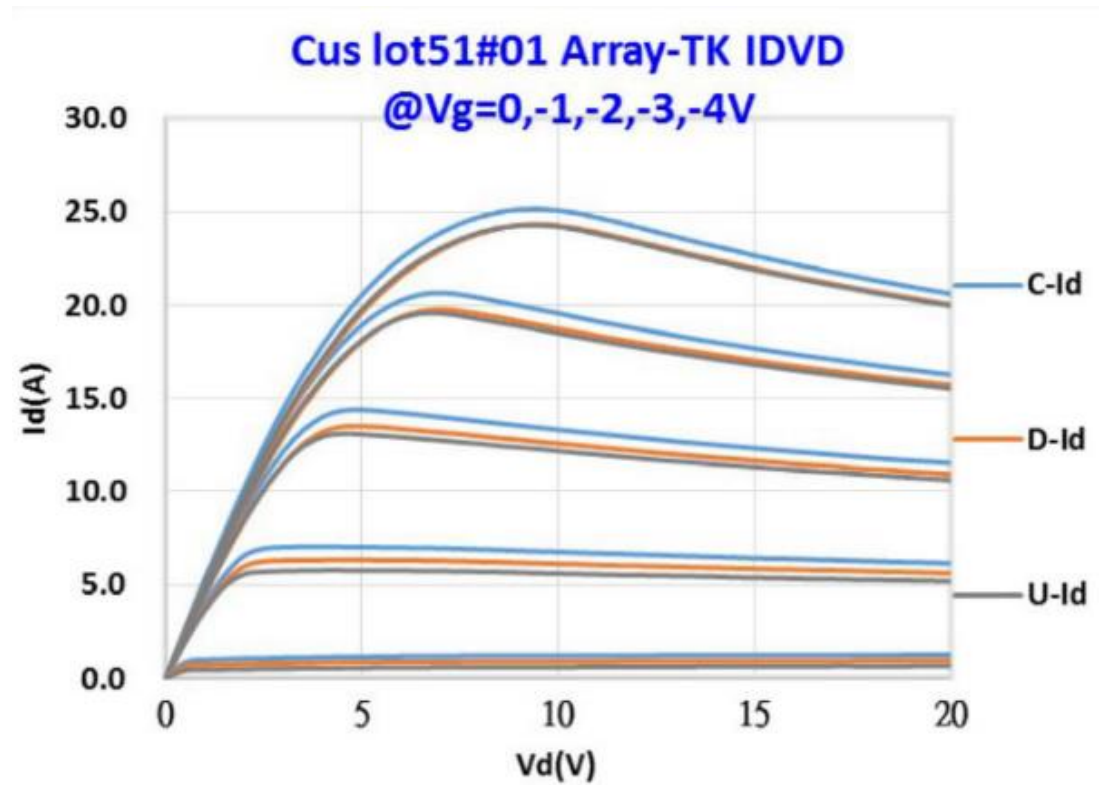
G PAD=450\*258μm

D PAD=3242\*400μm

S PAD=3242\*400μm

PAD Metal: Au PAD(Au thickness:3μm)

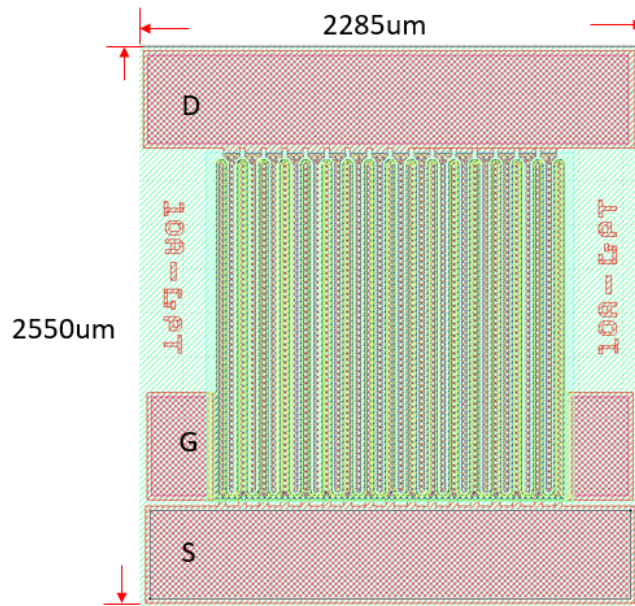
Total thickness:250μm ± 5%



# GPT YBE-025 15A Process Wafer data sheet

# GPT

## Appearance



## Specification:

15A HEMT

G PAD=450\*258um

D PAD=2186\*400um

S PAD=2186\*400um

PAD Metal: Au PAD(Au thickness:3um)

Total thickness:250um±5%

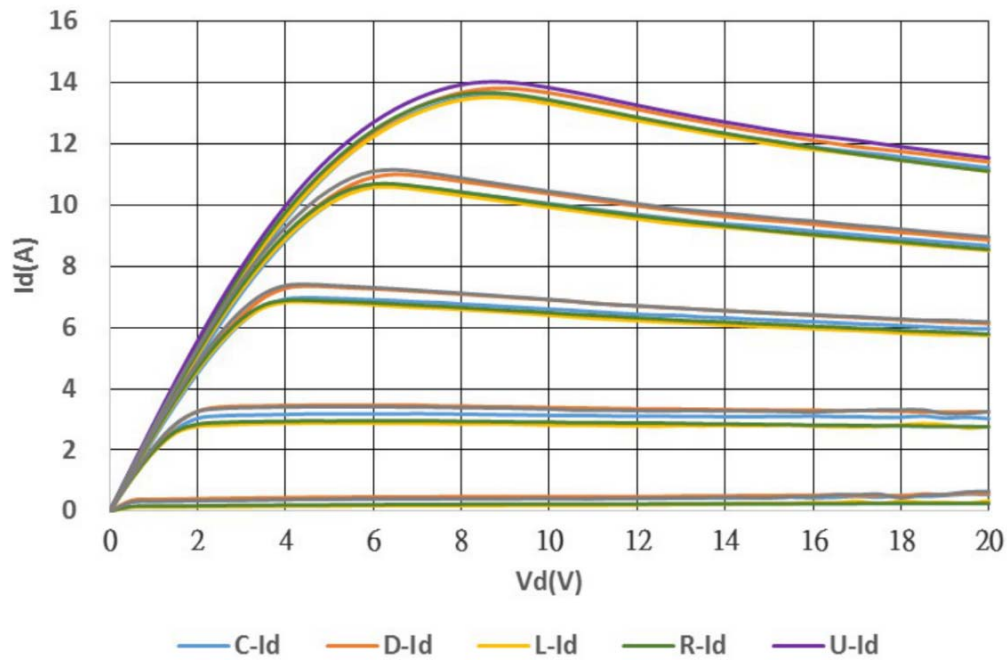
# GPT YBE-025 15A Process Wafer data sheet

# GPT

D-mode GaN HEMT Characteristics						
SYMBOL	PARAMETER	MIN	TYP	MAX	UNITS	CONDITIONS
$R_{DS(ON)}$	Drain-Source Resistance	326	360	500	mΩ	$I_{DS} = 3\text{ A}, V_{GS} = 0\text{ V}$
$V_P$	Pinch-off Voltage	-4.7	-4	-3	V	$V_{DS} = 10\text{ V}, V_{GS} = 0\text{ V}$
$I_{DSS}$	Drain-Source Leakage Current	20	356	991	μA	$V_{DS} = 300\text{ V}, V_{GS} = -10\text{ V}$
$I_{DON}$	Drain-Source Current	1.2	1.67	1.82	A	$V_{DS} = 0.6\text{ V}, V_{GS} = 0\text{ V}$

## D-HEMT power cell performance

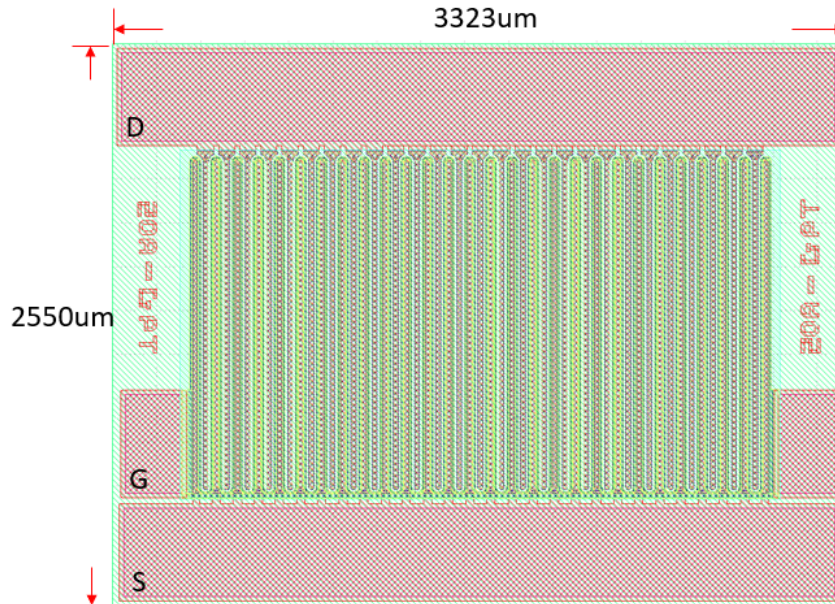
Cuslot53#01 Power Array Id-Vd @Vg=0,-1,-2,-3,-4V



# GPT YBE-015 25A Process Wafer data sheet

# GPT

## Appearance



## Specification:

25A HEMT

G PAD=450\*258um

D PAD=3242\*400um

S PAD=3242\*400um

PAD Metal: Au PAD(Au thickness:3um)

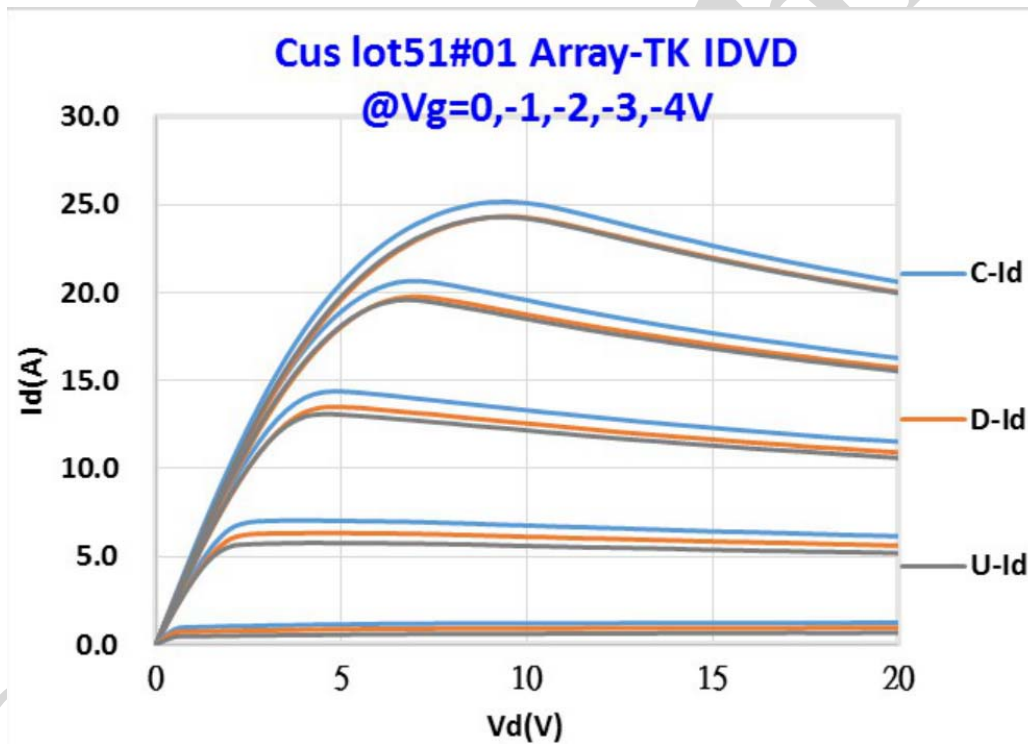
Total thickness:250um±5%

# GPT YBE-015 25A Process Wafer data sheet

# GPT

D-mode GaN HEMT Characteristics						
SYMBOL	PARAMETER	MIN	TYP	MAX	UNITS	CONDITIONS
$R_{DS(ON)}$	Drain-Source Resistance	184	202	349	m $\Omega$	$I_{DS} = 3\text{ A}, V_{GS} = 0\text{ V}$
$V_P$	Pinch-off Voltage	-4.8	-4.2	-2.6	V	$V_{DS} = 10\text{ V}, V_{GS} = 0\text{ V}$
$I_{DSS}$	Drain-Source Leakage Current	50	403	999	$\mu\text{A}$	$V_{DS} = 300\text{ V}, V_{GS} = -10\text{ V}$
$I_{DON}$	Drain-Source Current	1.6	2.4	2.6	A	$V_{DS} = 0.6\text{ V}, V_{GS} = 0\text{ V}$

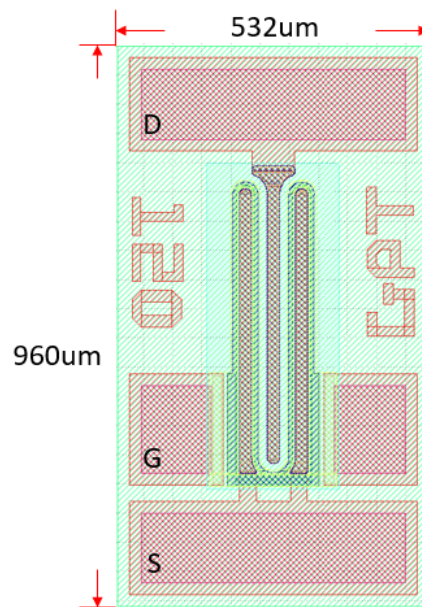
## D-HEMT power cell performance



# GPT YBE-045 140mA Process Wafer data sheet

# GPT

## Appearance



## Specification:

140mA HEMT

G PAD=150\*120μm

D PAD=452\*120μm

S PAD=452\*120μm

PAD Metal: Au PAD(Au thickness:3μm)

Total thickness:250μm±5%

# GPT YBE-045 140mA Process Wafer data sheet

# GPT

D-mode GaN HEMT Characteristics						
SYMBOL	PARAMETER	MIN	TYP	MAX	UNITS	CONDITIONS
$R_{DS(ON)}$	Drain-Source Resistance	16	17	20	$\Omega$	$I_{DS} = 120 \text{ mA}, V_{GS} = 0 \text{ V}$
$V_P$	Pinch-off Voltage	-2.8	-2.5	-2.3	V	$V_{DS} = 10 \text{ V}, V_{GS} = 0 \text{ V}$
$I_{DSS}$	Drain-Source Leakage Current	15	41	709	$\mu\text{A}$	$V_{DS} = 300 \text{ V}, V_{GS} = -5 \text{ V}$
$I_{DON}$	Drain-Source Current	58	68	79	mA	$V_{DS} = 1 \text{ V}, V_{GS} = 0 \text{ V}$

## D-HEMT power cell performance

